

## EAST Search History

Ref #	Hits	Search Query	Ds	Default Operator	Plurals	Time Stamp
L95	1	"20020180449"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:36
L94	1642	700/121.cds.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:36
L92	8180	L89 and (semiconductor wafer)	US-PGPUB; OR	OFF	2006/09/19 11:36	
L91	0	(semiconductor with tool) and (empirical with model)	US-PGPUB; OR	OFF	2006/09/19 11:36	
L17	3	(CFRDC) and simulat\$4	US-PGPUB; OR	ON	2006/09/19 11:36	
L93	805	703/22.cds.	US-PGPUB; OR	OFF	2006/09/19 11:34	
L90	1444	L89 and geometric	US-PGPUB; OR	OFF	2006/09/19 11:34	
L89	19972	(data parameter) with (etch deposition coating lithography (thermal adj annealing))	US-PGPUB; OR	OFF	2006/09/19 11:34	
L88	740	(ELIEN) and simulat\$4	US-PGPUB; OR	ON	2006/09/19 11:34	
L87	5	"10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	US-PGPUB; OR	OFF	2006/09/19 11:34	
L86	1	(tool) and (empirical with model)	US-PGPUB; OR	OFF	2006/09/19 11:34	
L85	3	(CFRDC) and simulat\$4	US-PGPUB; OR	ON	2006/09/19 11:34	

## EAST Search History

L84	3	L49 and (converg\$6)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L83	2	L54 and (adjust\$6).cdm.	US-PGPUB; OR	OFF	2006/09/19 11:34	
L82	4	L81 and Geometri\$4	US-PGPUB; OR	OFF	2006/09/19 11:34	
L81	19	(US-20030078738-\$ or US-20040078319-\$ or US-20040102934-\$ or US-200500165947-\$).cdm. (US-5719796-\$ or US-6571371-\$ or US-6615097-\$ or US-6628899-\$ or US-6643616-\$ or US-6728591-\$ or US-6757645-\$ or US-6763277-\$ or US-6774998-\$ or US-6802045-\$ or US-6812045-\$ or US-5905895-\$).cdm. •	US-PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L80	0	(semiconductor and tool) and (empirical with model) (ANSYS ) with simulat\$4	US-PGPUB; OR	OFF	2006/09/19 11:34	
L79	127		US-PGPUB; OR	ON	2006/09/19 11:34	
L78	0	(processing with tool) and (empirical with model)	US-PGPUB; OR	OFF	2006/09/19 11:34	
L77	1	L54 and (nonlinear+\$3 multivariate).cdm.	US-PGPUB; OR	OFF	2006/09/19 11:34	
L76	5	L75 and empirical	US-PGPUB; OR	OFF	2006/09/19 11:34	
L75	5	"10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	US-PGPUB; OR	OFF	2006/09/19 11:34	
L74	5	L54 and control\$6	US-PGPUB; OR	OFF	2006/09/19 11:34	
L73	9	L49 and (adjust)	US-PGPUB; OR	ON	2006/09/19 11:34	
L72	1	L49 and (calibration)	US-PGPUB; OR	OFF	2006/09/19 11:34	
L71	2	L70 and (rate).cdm.	US-PGPUB; OR	OFF	2006/09/19 11:34	

EAST Search History

3/19/2006 11:39:38 AM  
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C:\Documents and Settings\

EAST Search History

L62	4	(US-20050016947-\$) did, or (US-66225497-\$) did, or (US-57119795-\$) or US-53077116-\$ or US-6802045-\$ or did.	US-PGPUB; USPAT	OR	OFF	2005/09/19 11:34
L61	5	"10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	US-PGPUB;	OR	OFF	2005/09/19 11:34
L60	3	(Input with size) with (etch deposition coating lithography (thermal adj annealing)) with (semiconductor wafer)	US-PGPUB;	OR	OFF	2005/09/19 11:34
L59	5	(geometric with parameters) with (data parameter) with (etch deposition coating lithography (thermal adj annealing))	US-PGPUB;	OR	OFF	2005/09/19 11:34
L58	87	geometric and (data parameter) with (etch deposition coating lithography (thermal adj annealing)) with (semiconductor wafer)	US-PGPUB;	OR	OFF	2005/09/19 11:34
L57	29	geometric with (data parameter) with (etch deposition coating lithography (thermal adj annealing))	US-PGPUB;	OR	OFF	2005/09/19 11:34
L56	297	(ANSYS ) and simulat&#4	US-PGPUB;	OR	ON	2005/09/19 11:34
L55	50	("5886906" "5886363" "6031246" "5049616" "6093161" "4268951" "4782253" "5004774" "4246742" "6030491" "6168891" "6178544" "6207630" "3343878" "4443532" "4481049" "4491530" "4500798" "4582682" "5597985" "6021537" "4615782" "9769817" "4792893" "4801713" "4822716" "4842986" "4873661" "4952666" "4969748" "4984902" "5018166" "4999282" "5006717" "5017453" "4959516" "5198520" "5213996" "5243538" "5248956" "5288604" "5312723" "5312724" "5330884" "5331420" "5336752" "5330939").pn. "10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	USOCR; EPO; JPO; DERWENT; IBM_TDB USPAT	OR	OFF	2005/09/19 11:34
L54	5	US-PGPUB	OR	OFF	2005/09/19 11:34	

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## EAST Search History

L53	163	(FLUENT) and simulate\$4 and (semiconductor water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB US-PGPUB; OR USPAT	OR	ON	2006/09/19 11:34	
L52	6	(empirical with model)		OFF	OFF	2006/09/19 11:34	
L51	2	(physical with geometric with parameters) with (data parameter) with (etch deposition coating lithography, (thermal adj annealing))	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L50	0	semiconductor with tool with empirical with model	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L49	19	(US-20030078738-\$ or US-20040102934-\$ or US-200401029319-\$ or US-20050016947-\$).did. or (US-5719796-\$ or US-6571371-\$ or US-6615097-\$ or US-6628809-\$ or US-6643616-\$ or US-6728391-\$ or US-6757645-\$ or US-6763277-\$ or US-6774998-\$ or US-6802045-\$ or US-6812045-\$ or US-6905895-\$). did. or (US-58656437-\$ or WO-200177979-\$ or WO-200277585-\$ or US-20030153302-\$ or US-20040078319-\$ or US-20050010394-\$).did.	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L48	5433	(ANSYS FLUENT CRDC (Monte adj Carlo)) and simulate\$4	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB US-PGPUB; OR USPAT	OR	ON	2006/09/19 11:34	
L47	6	(empirical with model)		OFF	OFF	2006/09/19 11:34	
L46	1	(tool) and (empirical with model)	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L45	0	(semiconductor and tool) and (empirical with model)	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L44	0	(processing with tool) and (empirical with model)	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L43	0	(semiconductor with tool) and (empirical with model)	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	
L42	0	semiconductor with tool with empirical with model	US-PGPUB; OR USPAT	OFF	OFF	2006/09/19 11:34	

## EAST Search History

L41	5	L40 and empirical	US-PGPUB OR US-PGPUB	OR	OFF	2006/09/19 11:34	
L40	5	"10/673301" "10/673583"	US-PGPUB OR US-PGPUB	OR	OFF	2006/09/19 11:34	
L39	5	"10/673301" "10/673583"	US-PGPUB OR US-PGPUB	OR	OFF	2006/09/19 11:34	
L38	805	703/22.ods.	US-PGPUB; USPAT	OR	OFF	2006/09/19 11:34	
L37	4	(US-20050016947-\$).did. or (US-56255497-\$ or US-5629877-\$ or US-537116-\$ or US-5719796-\$ or US-6802045-\$ or US-6812045-\$).	US-PGPUB; USPAT	OR	OFF	2006/09/19 11:34	
L36	50	"5340657" "5374327" "5382823" "5384289" "54004335" "5406309" "5409547" "5418397" "5427716" "542644" "5455928" "5459052" "5474884" "5478072" "5490953" "5493501" "5495417" "5511005" "5517140" "5523022" "5558964" "5561612" "5571662" "5593608" "5596695" "5617322" "5619159" "5629877" "5637151" "5650947" "5654904" "5658705" "5663889" "5672468" "5672902" "5684723" "5694325" "5694502" "5699264" "5706200" "570957" "5712794" "5714678" "5715170" "5725974" "5728514" "5731626" "5736024" "5737242" "5745388").pn.	USPAT	OR	OFF	2006/09/19 11:34	
L35	50	("5886906" "5886363" "5631246" "6095161" "6268951" "4982252" "5004774" "5446742" "6030491" "6168891" "6178544" "6207630" "6434878" "6443532" "4881046" "4915130" "500798" "4930387" "4954921" "4981706" "4982683" "4997985" "4998153" "4915798" "4769817" "4792895" "4801713" "4822716" "4842986" "4873651" "4957666" "4969748" "4984902" "4989166" "4999282" "5006717" "5017452" "5029516" "5198520" "5212996" "5243538" "5248956" "5288604" "5312723" "5312724" "533084" "5331420" "5336752" "5339035").pn.	USPAT	OR	OFF	2006/09/19 11:34	
L34	5	"10/673301" "10/673583" "10/673467" "10/673507"	US-PGPUB	OR	OFF	2006/09/19 11:34	

## EAST Search History

L33	3	(input with size) with (etch deposition coating lithography (thermal adj annealing)) with (semiconductor wafer)	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L32	5	(geometric with parameters) with (data parameter) with (etch deposition coating lithography (thermal adj annealing))	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L31	2	(physical with geometric with parameters) with (data parameter) with (etch deposition coating lithography (thermal adj annealing)) with (semiconductor lithography (thermal adj annealing))	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L30	87	geometric and (data parameter) with (etch deposition coating lithography (thermal adj annealing)) with (semiconductor wafer)	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L29	29	geometric with (data parameter) with (etch deposition coating lithography (thermal adj annealing))	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L28	1444	L26 and (semiconductor wafer)	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L27	8180	L26 and (semiconductor wafer)	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L26	19972	(data parameter) with (etch deposition coating lithography (thermal adj annealing))	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L25	4	L24 and Geometric\$4	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L24	19	(US_20030078738-\$ or US_20040078319-\$ or US_20040102934-\$ or US_2005016947-\$).did. or (US_5719796-\$ or US_6571371-\$ or US_6615097-\$ or US_6643616-\$ or US_6757645-\$ or US_6763277-\$ or US_6774998-\$ or US_6802045-\$ or US_6812045-\$ or US_6905895-\$). did. or (US_5866437-\$ or US_20030133302-\$ or US_20040078319-\$ or US_2005010319-\$).did.	US_PGPUB; USPAT	OR	OFF	2006/09/19 11:34
L23	5	"10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	US_PGPUB	OR	OFF	2006/09/19 11:34

## EAST Search History

L22	163	(FLUENT) and simulat\$4 and (semiconductor wafer)	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L21	127	(ANSYS ) with simulat\$4	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L20	215	(FLUENT) with simulat\$4	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L19	1642	700/121.cds.	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L18	740	(FLUENT) and simulat\$4	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L16	297	(ANSYS ) and simulat\$4	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L15	5433	(ANSYS FLUENT CFRDC (Monte adj Caro)) and simulat\$4	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34
L14	3	L3 and (converg\$5)	US_PGPUB; USPAT; USOCR; EPO; JPO; DERVENT; IBM_TDB	OR	ON	2006/09/19 11:34

### EAST Search History

### EAST Search History

L1	L2	L3	L4	L5	L6	L7	L8	L9	L10	L11	L12	L13
L1	L2	L3	L4	L5	L6	L7	L8	L9	L10	L11	L12	L13
L1	9	L3 and (adjust)										
L12	1	L3 and (calibration)	US-PGPUB; OR	ON	2006/09/19 11:34							
L11	3	L3 and (nonlinear\$3 multivariate)	US-PGPUB; OR	OFF	2006/09/19 11:34							
L10	1	L6 and (nonlinear\$3 multivariate).dim.	US-PGPUB; OR	OFF	2006/09/19 11:34							
L9	2	L6 and (adjust\$6).clm.	US-PGPUB; OR	OFF	2006/09/19 11:34							
L8	3	L6 and (control\$6).clm.	US-PGPUB; OR	OFF	2006/09/19 11:34							
L7	5	L6 and control\$6	US-PGPUB; OR	OFF	2006/09/19 11:34							
L6	5	"10/673501" "10/673583" "10/673138" "10/673467" "10/673507"	US-PGPUB; OR	OFF	2006/09/19 11:34							
L5	8	L4 and rate	US-PGPUB; USPAT	OFF	2006/09/19 11:34							
L4	19	(US-20030078738-\$ or US-20040078319+\$ or US-20040102934+\$ or US-20050016947-\$).did. or (US-5719796-\$ or US-6571371-\$ or US-6615097-\$ or US-6628809-\$ or US-6643616-\$ or US-67288591-\$ or US-6757645-\$ or US-6763277-\$ or US-6774998-\$ or US-6812045-\$ or US-681437-\$ or US-5866437-\$ or US-20030135302+\$ or US-20040078319+\$ or US-20050010319-\$).did.	US-PGPUB; USPAT	OFF	2006/09/19 11:34							
L3	19	(US-20030078738-\$ or US-20040078319+\$ or US-20040102934+\$ or US-20050016947-\$).did. or (US-5719796-\$ or US-6571371-\$ or US-6615097-\$ or US-6628809-\$ or US-6643616-\$ or US-67288591-\$ or US-6757645-\$ or US-6763277-\$ or US-6774998-\$ or US-6812045-\$ or US-681437-\$ or US-5866437-\$ or WO-200177979-\$ or WO-200277589-\$ or US-20030135302+\$ or US-20040078319+\$ or US-20050010319-\$).did.	US-PGPUB; USPAT	OFF	2006/09/19 11:34							
L2	2	L1 and (rate).clm.	US-PGPUB	OFF	2006/09/19 11:34							